



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:
VADIM YEVGENYEVICH BANINE et al.
Application No.: 10/748,851

Confirmation Number: 2813

Group Art Unit: 2851

Filed: December 31, 2003

Examiner: Della J. Rutledge

Title: LITHOGRAPHIC APPARATUS HAVING A DEBRIS-MITIGATION SYSTEM, A SOURCE FOR PRODUCING EUV RADIATION HAVING A DEBRIS MITIGATION SYSTEM AND A METHOD FOR MITIGATING DEBRIS

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Mail Stop Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In the Office Action dated September 12, 2006, the Examiner has set forth "Reasons for Allowance." Applicants respectfully traverse these Reasons. Specifically, it is submitted that the subject matter of the allowed claims are patentable for their respective recitations of claimed combinations as a whole. That is, the patentability of the claims rests on the combination of recited elements and limitations. As such, Applicants submit that no one element or limitation in particular should be deemed to impart or be required for patentability of the claims. Furthermore, Applicants also submit that the dependent claims are allowable not only for their dependence on the allowed independent claims, but also for the additional subject matter recited in each of those dependent claims.

Respectfully submitted,

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